

ELECTRON BEAM ANALYZER

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Abstract

PROBLEM TO BE SOLVED: To achieve a three-dimensional analysis on bulk samples.

SOLUTION: Inside an analysis chamber 3, an electron beam irradiation part 4 is provided to generate electron beams B made to irradiate a sample S, an X-ray spectral detector 5 which spectrally detects X rays R generated from the sample, an electron detector 6 which detects electrons E generated from the sample and the like. A glow discharging part 8 is arranged near an analyzing position P1 where the sample is irradiated with the electron beams--as an etching position P2. A sample stage 7 is provided to move the sample S between the two positions. After the etching of the surface of the sample at the P2, analysis on the surface of the sample is repeated at the P1, thereby achieving a three-dimensional analysis for obtaining the three-dimensional information distribution of the sample.

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